Docket No.

263261US0PCT

IN RE APPLICATION OF: Hitoshi KATO, et al.

SERIAL NO: 10/518,025

FILED:

December 15, 2004

FOR:

METHOD OF CVD FOR FORMING SILICON NITRIDE FILM ON SUBSTRATE

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

Transmitted herewith is an Amendment in the above-identified application.

- No additional fee is required
- ☐ Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.
- Certified English translation of Japanese Priority Document 2003-016659 Additional documents filed herewith:

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS		RATE	•	CALCULATIONS
TOTAL	15	MINUS	20	0	х	\$50	=	\$0.00
INDEPENDENT	1	MINUS	3	0	х	\$200	=	\$0.00
		☐ MULTIPL	E DEPENDENT	CLAIMS	+	\$360	=	\$0.00
			TOTAL	OF ABOVE CA	LCU	JLATIC	NS	\$0.00
		☐ Reduction	by 50% for filing	by Small Entity				\$0.00
		☐ Recordation	on of Assignment		+	\$40	=	\$0.00
				Make to take the state		TOT	ΆL	\$0.00

\square A check in the amount of \$0.00 is attac
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- ☐ Credit card payment form is attached to cover the fees in the amount of **§0.00**
- Please charge any additional Fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.
- If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

OBLON, SPIVAK, McCLELLAND,

MAIER & NEUSTADT, P.C.

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